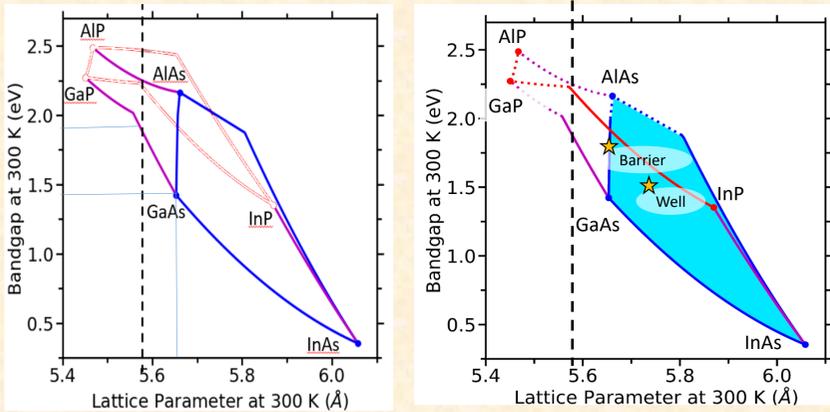


High Polarization Photocathodes: UCSB & JLab Re-visiting InAlGaAs/AlGaAs

Marcy Stutzman (JLab) Aaron Engle & Chris Palmstrøm (UCSB), Greg Blume (ODU)

Composition



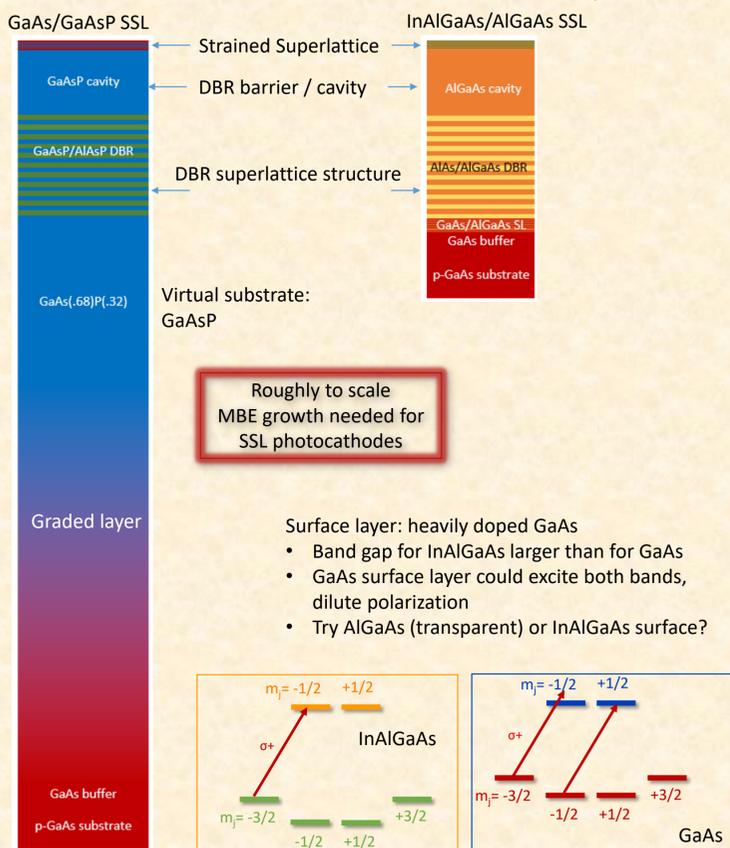
GaAs/GaAsP superlattice

1. Requires graded layer
2. High vapor residue
3. Growth Temp mismatch
4. Wavelength and strain dependent
5. DBR structure: different composition
6. Great Results: 85+% Pol, 1% QE

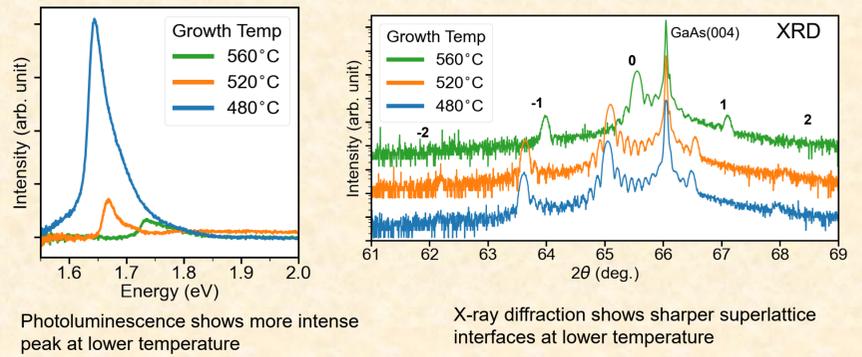
InAlGaAs/AlGaAs superlattice

1. Grow AlGaAs directly on GaAs
2. Common MBE elements
3. Good temperature match
4. Wavelength and strain independent
5. DBR structure very compatible
6. Best Results: comparable

Based on Mamaev et al., Appl. Phys. Lett. 93, 081114 (2008)



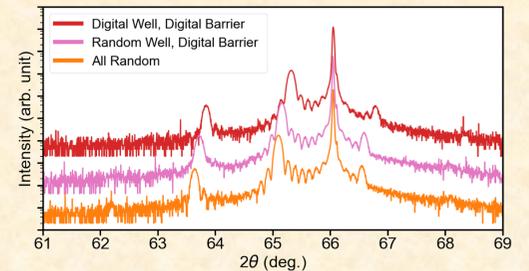
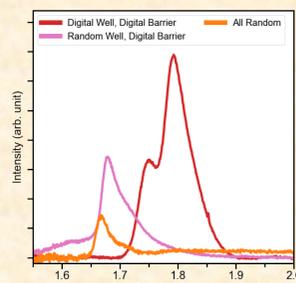
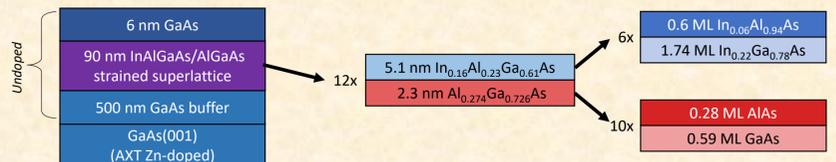
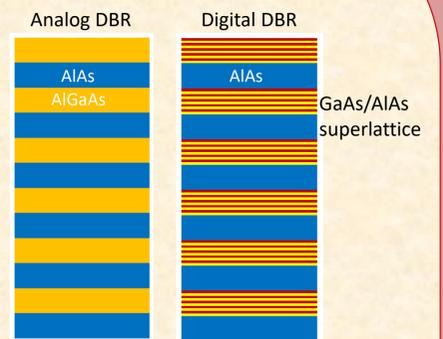
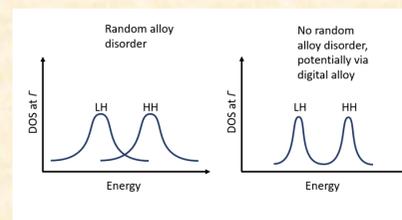
Temperature Variation



Analog vs. Digital Growth

Quaternary Alloy InAlGaAs can introduce non-uniformity

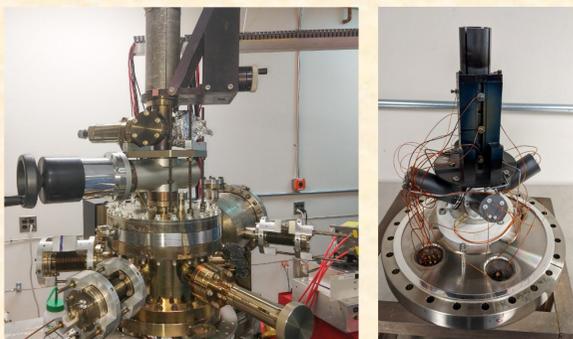
Digital alloy: Layers of simpler alloy instead of co-deposition



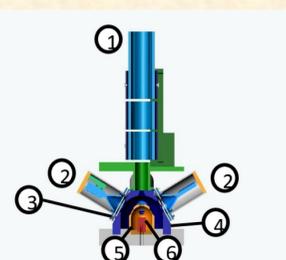
PL: improves with digital alloy barriers or wells

XRD: Similar to analog

JLab MicroMott Polarimeter

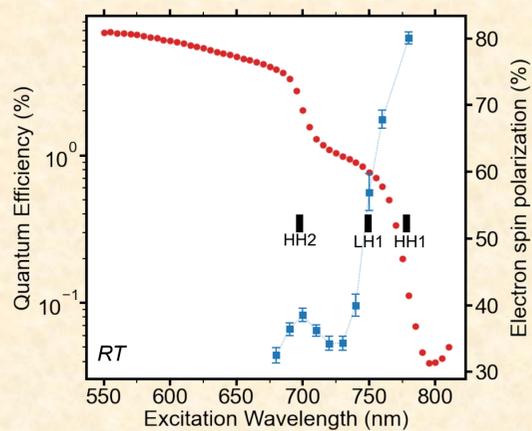


1. Lenses
2. CEM
3. Grids
4. Outer Hemi
5. Inner Hemi
6. Target



McCarter, J. L., Stutzman, M. L., Trantham, K. W., Anderson, T. G., Cook, A. M., and Gay, T. J. A low-voltage retarding-field Mott polarimeter for photocathode characterization. United States: N. p., 2010. Web. doi:10.1016/j.nima.2010.02.123.

Results & Next Steps



- 520°C growth temperature
- 82.5% Polarization, 0.34% QE at 780 nm
 - Decent first try
 - Heavy Hole/Light hole bands split
 - ~50 meV

- More samples ready to test
- 480°C and 560°C: samples 198, 199
 - Increased strain: sample 144
 - Higher dopant top and band gap shift: sample 143
 - Digital alloy barrier layer: Sample 202

Awaiting polarimetry feedback

- DBR structure grown and analyzed
- Ready to grow SSL on DBR